

ABSTRACT OF THE DISCLOSURE

To provide a pattern formation method capable of forming a pattern by cleaning a liquid droplet ejection head without exerting an effect on a liquid droplet ejection operation, when the liquid droplet ejection head stored with a storage solution is used again, a pattern formation method of forming a film pattern by disposing liquid droplets of a functional solution on a substrate, includes: filling a passage including a liquid droplet ejection head to dispose the liquid droplets and a conduit to feed the functional solution to the liquid droplet ejection head with purified water; filling the passage with a solvent dissolving both a solvent contained in the functional solution and the purified water; filling the passage with the solvent contained in the functional solution; forming banks corresponding to the film pattern on the substrate; and disposing the liquid droplets into grooves between the banks with the liquid droplet ejection head.